



Processor Architecture Laboratory
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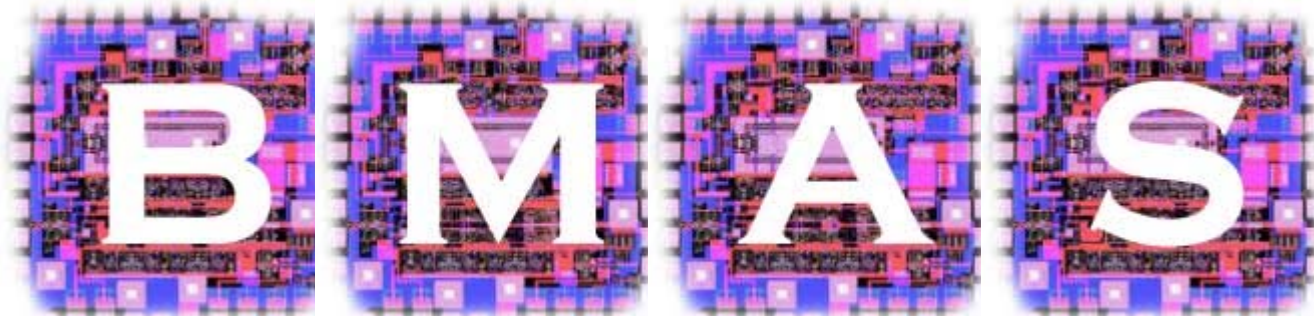


Reduced Order Models of Integrated RF Spiral Inductors with Geometrical and Technological Automatic Parameterization

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Motivation

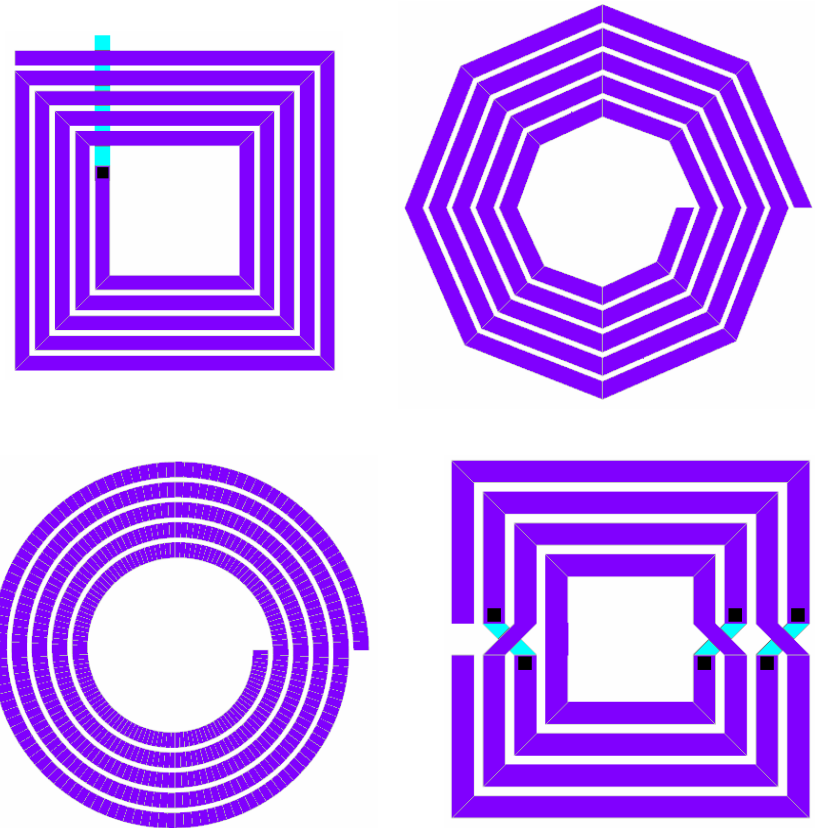
- Advancement in Wireless Communication Industry:
 - Smaller, Cheaper transceivers in Gigahertz Range.
 - On-Chip Inductive elements address both these requirements.
- Accurate tools for predicting and optimizing the characteristics of on-chip Inductive elements.

Spiral RF Inductors

- Inductance, L.
- Quality of Inductor, Q.

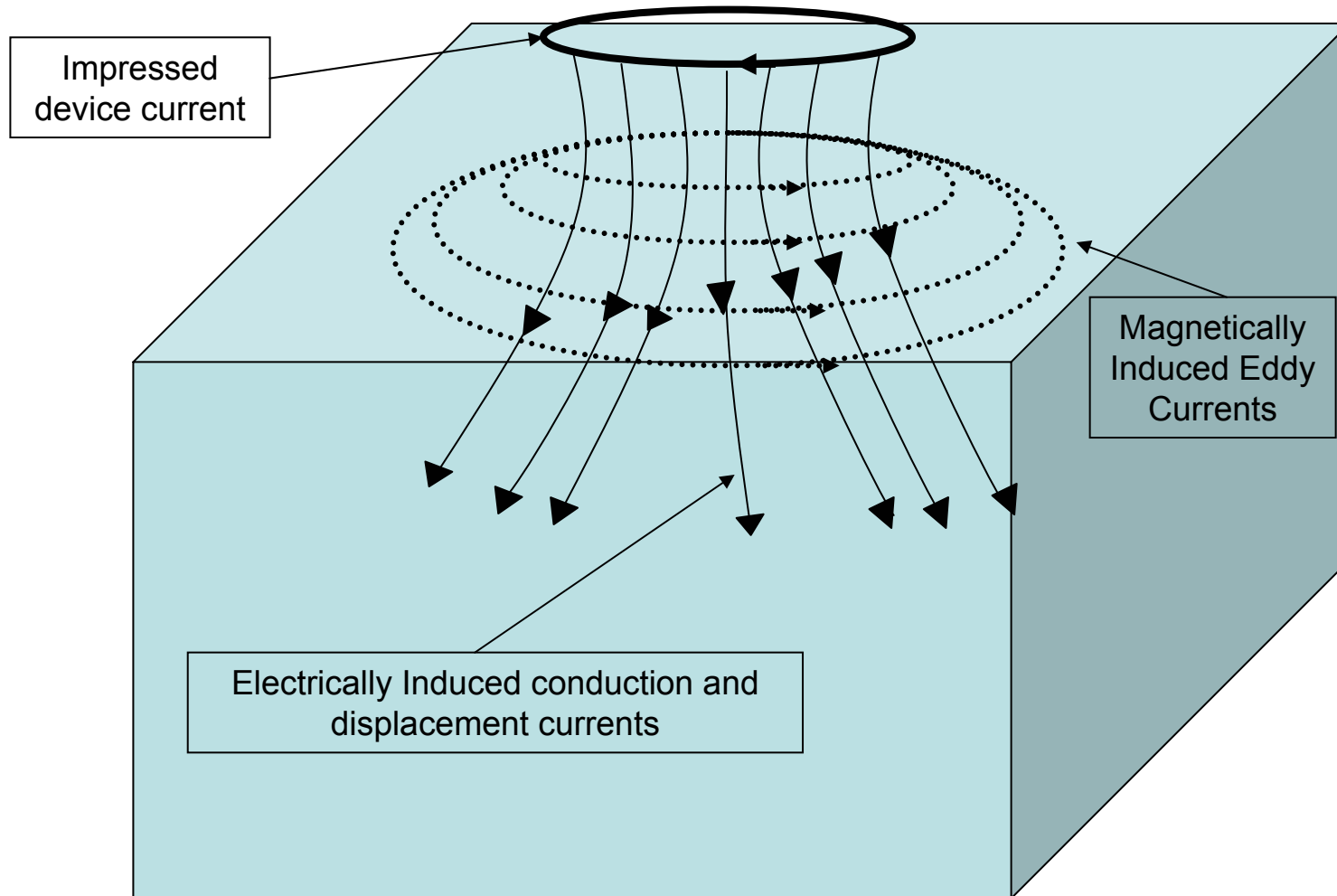
$$Q \propto \frac{E_{stored}}{E_{dissipated}}$$

- Energy Dissipation
 - Displacement Current
 - Eddy Current



A Square Spiral Inductor

Parasitic Losses



Typical parasitic Losses in Spiral Inductors

Timeline

- Ruehli et al, 1974
 - Concept of PEEC.
- Pettenpaul et al, 1988
 - Model each spiral segment individually.
- Niknejad , PhD Dissertation 2000.
 - Model the Substrate & Eddy Current losses.
 - Based on full simulation of Spiral using PEEC.
- Daniel et al., 2003 proposed geometrical parameterization technique for Spiral inductors.
 - Can't model the substrate losses.

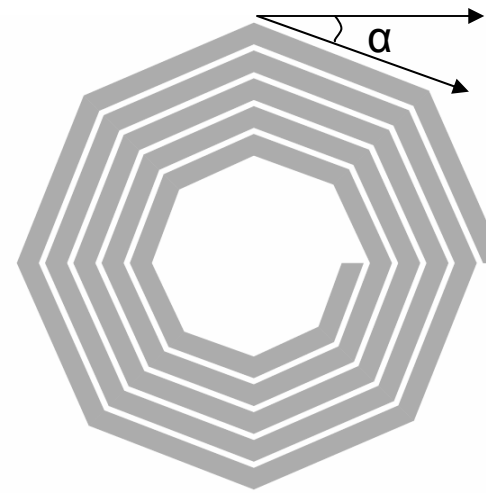
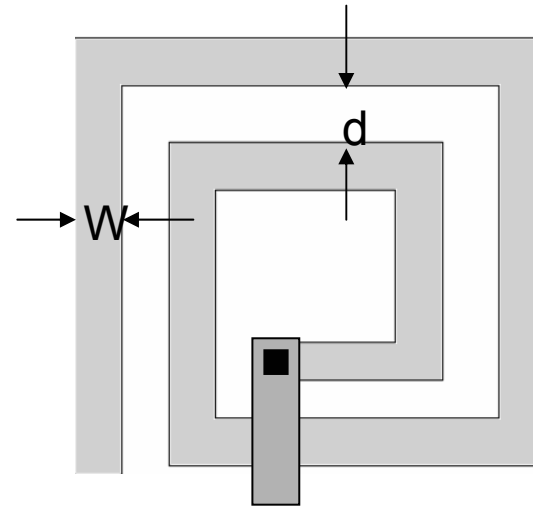
Contribution

- In this paper : Substrate Aware Geometrical Parameterization for Spiral Inductors.
 - Model Substrate Losses
 - Parameterized
 - More accurate
 - Extendable

Parameterization

- Design Parameters

- ✓ Width of Wire, w .
- ✓ Separation between turns, d .
- ✓ Frequency of operation.
- Height of Inductor from substrate.
- Number of turns.
- Number of sides, or angle of turn, α .



Outline

- ➔ Theoretical Background
 - Volume Integral Equations
 - PEEC Technique
- Substrate Modeling
- Parameterization & Model Reduction
- Results
- Conclusions & Future Work

Volume Integral Equations

- Current-Voltage relation

$$\frac{J(r)}{\sigma} + j\omega \frac{\mu}{4\pi} \int_V \frac{J(r')}{|r - r'|} dr' = -\nabla \phi,$$

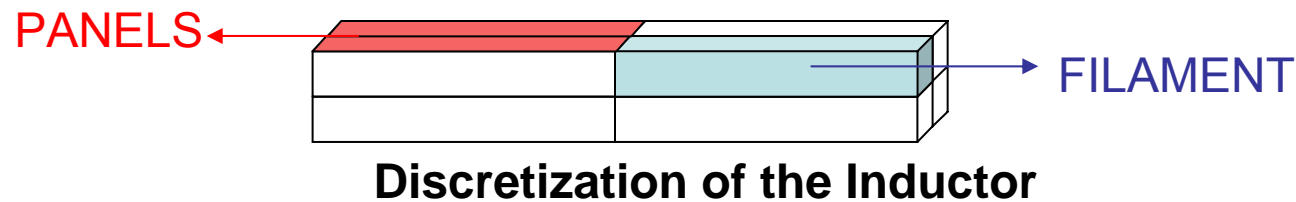
- Charge-Voltage relation

$$\frac{1}{4\pi\epsilon} \int_S \frac{\rho(r')}{|r - r'|} dr' = \phi(r'),$$

- Charge and current conservation

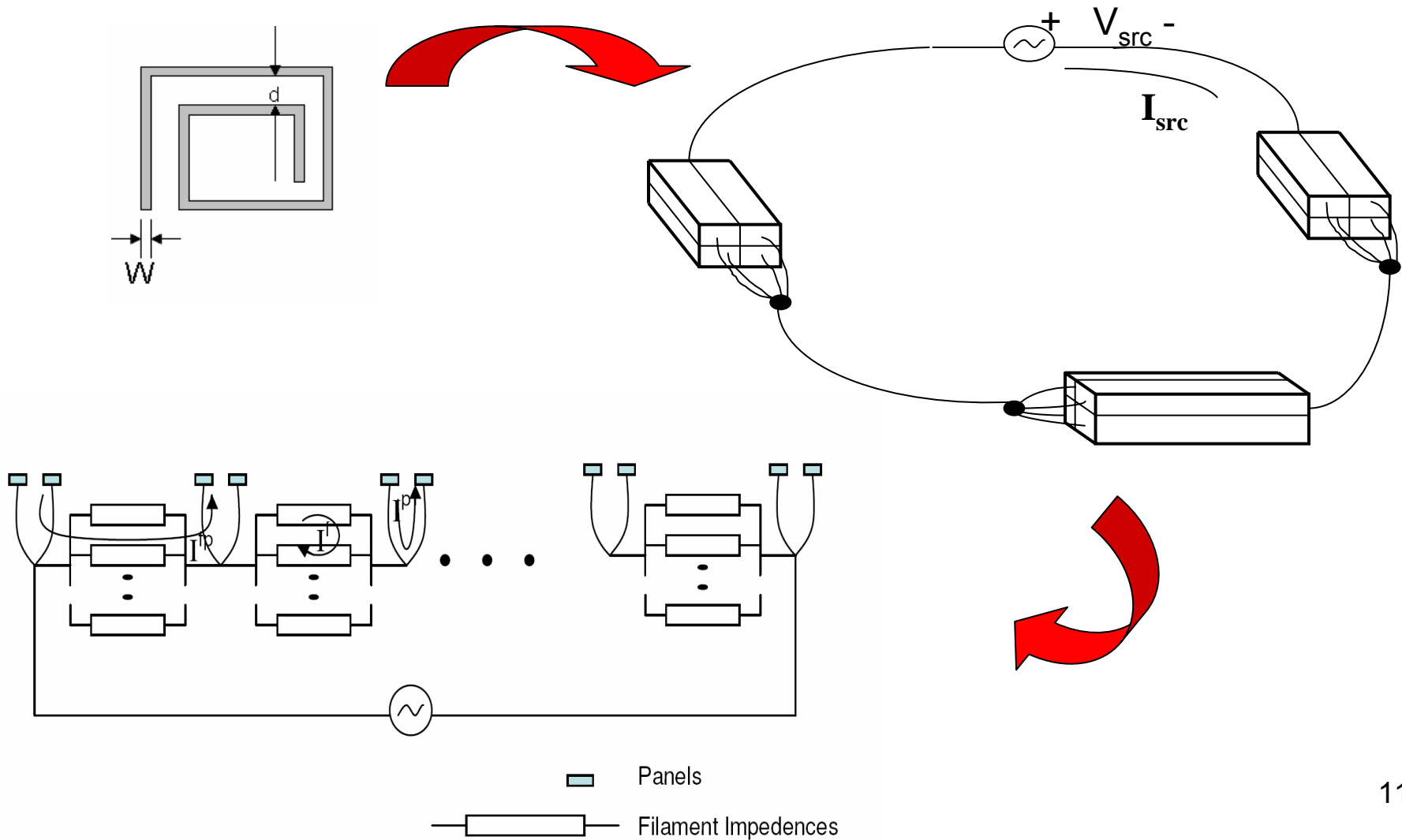
$$\hat{n} \cdot J(r) = j\omega\rho(r) \quad \nabla \cdot J(r) = 0$$

PEEC Technique [Ruehli 74]

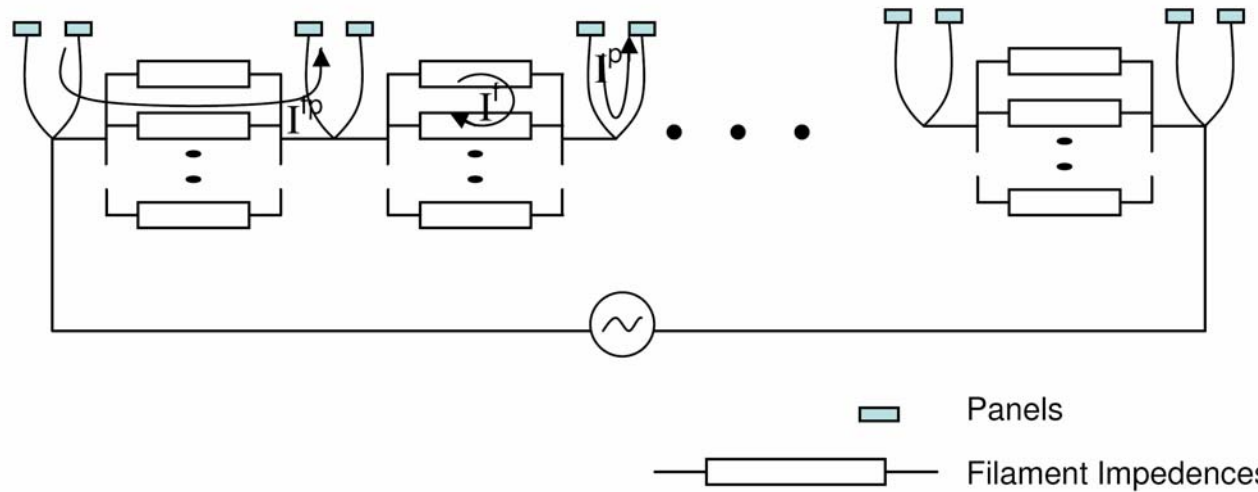


- Discretization
 - Meshed into 3D Filaments and 2D Panels.
 - Filaments capture the constant current density.
 - Panels capture the constant charge density on surface.
- Non-uniform discretization
 - Capture skin effects.
 - Boundary effects.

PEEC Construction



Modeling PEEC Circuit



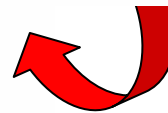
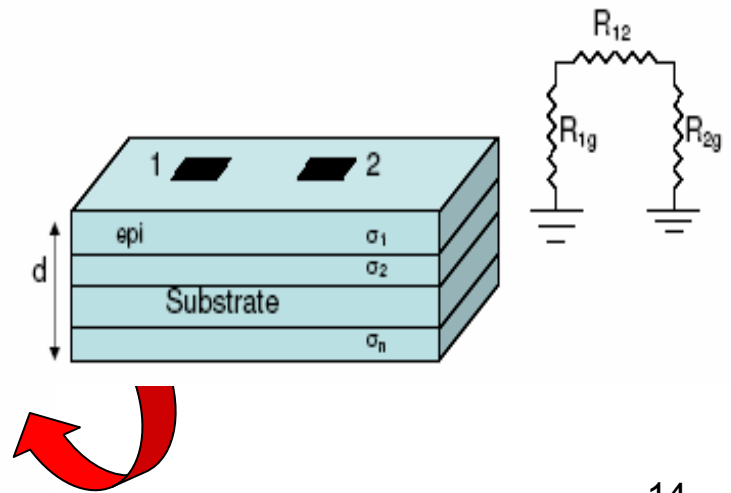
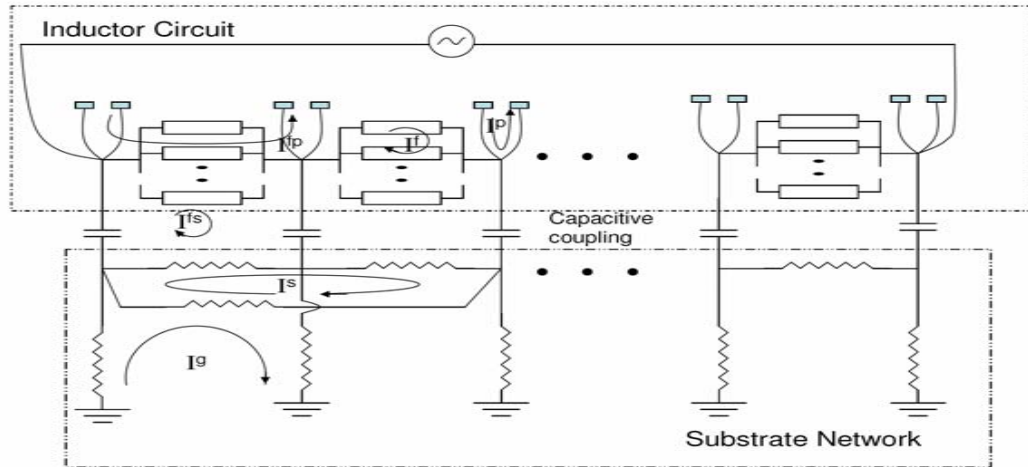
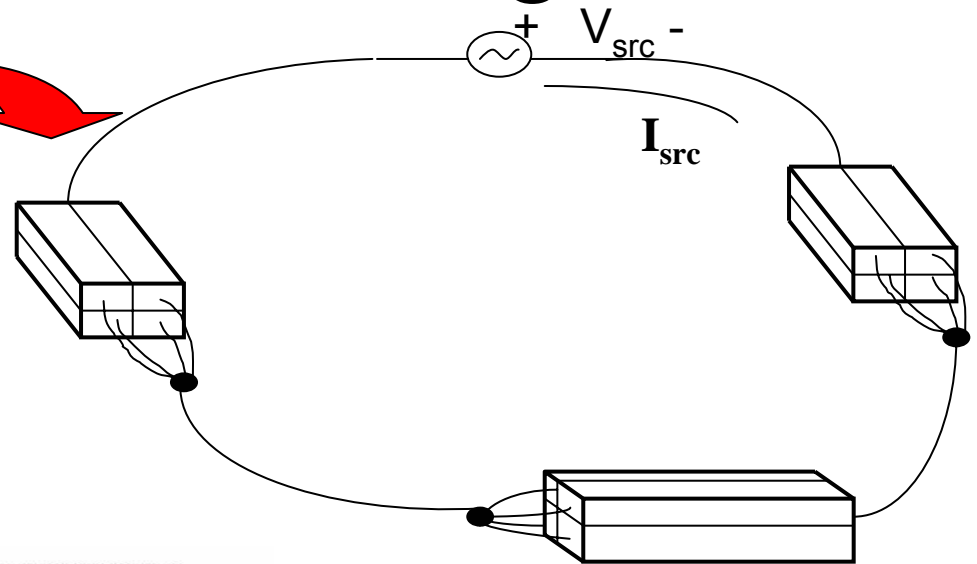
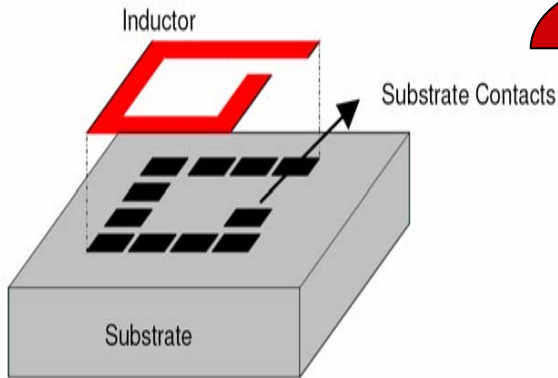
$$s \begin{bmatrix} M_f L_f M_f^T & 0 \\ 0 & P^{-1} \end{bmatrix} \begin{bmatrix} I_m \\ \phi \end{bmatrix} = - \begin{bmatrix} M_f R_f M_f^T & M_p \\ -M_p^T & 0 \end{bmatrix} \begin{bmatrix} I_m \\ \phi \end{bmatrix} + \begin{bmatrix} V_{m,s} \\ 0 \end{bmatrix}$$

$$sLx = -Rx + BV_{src}$$

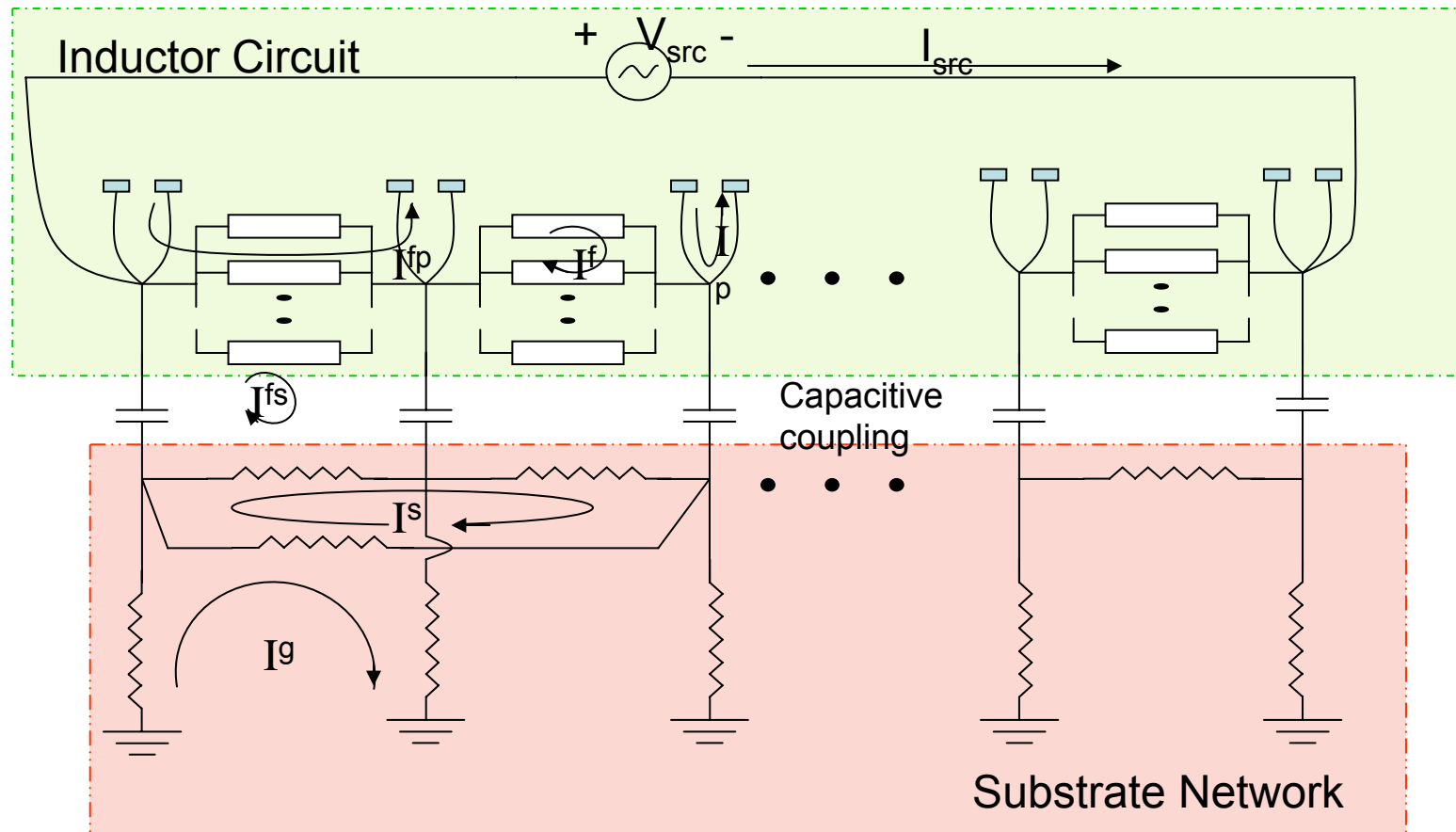
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Substrate Modeling



Substrate Modeling



Substrate Modelling

Green Function based
FFT technique.

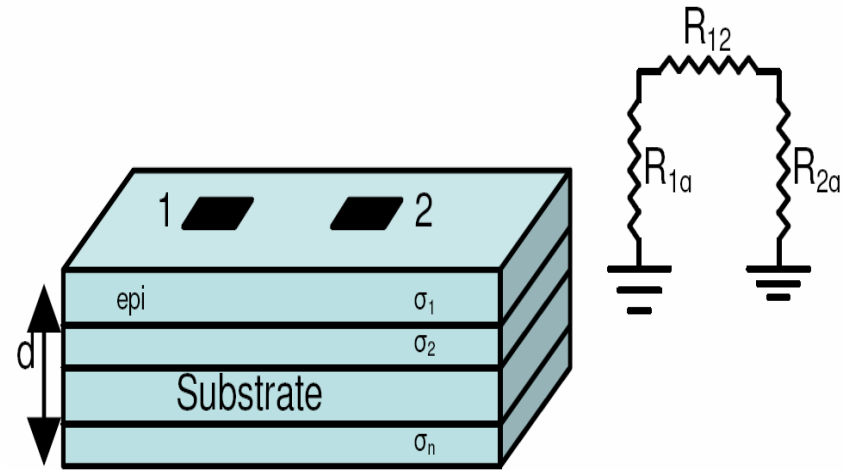
$$\phi(r) = \int_V \rho(r') G(r, r') d^3 r'$$

$$[Q] = [c][\phi]$$

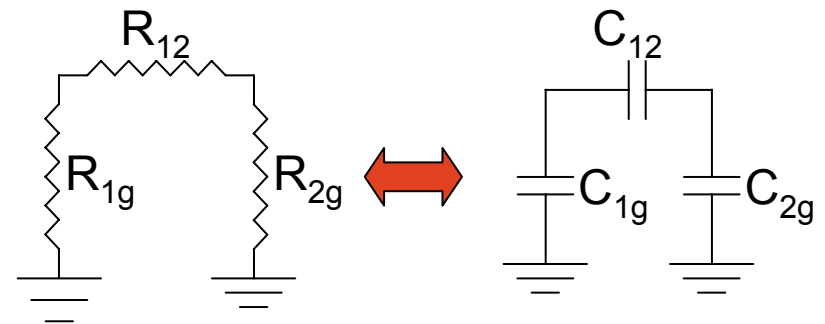
$$C_{ij} = -c_{ij}$$

$$C_{ig} = c_{ii} + \left(\sum_{j=1}^N c_{ij} \right)$$

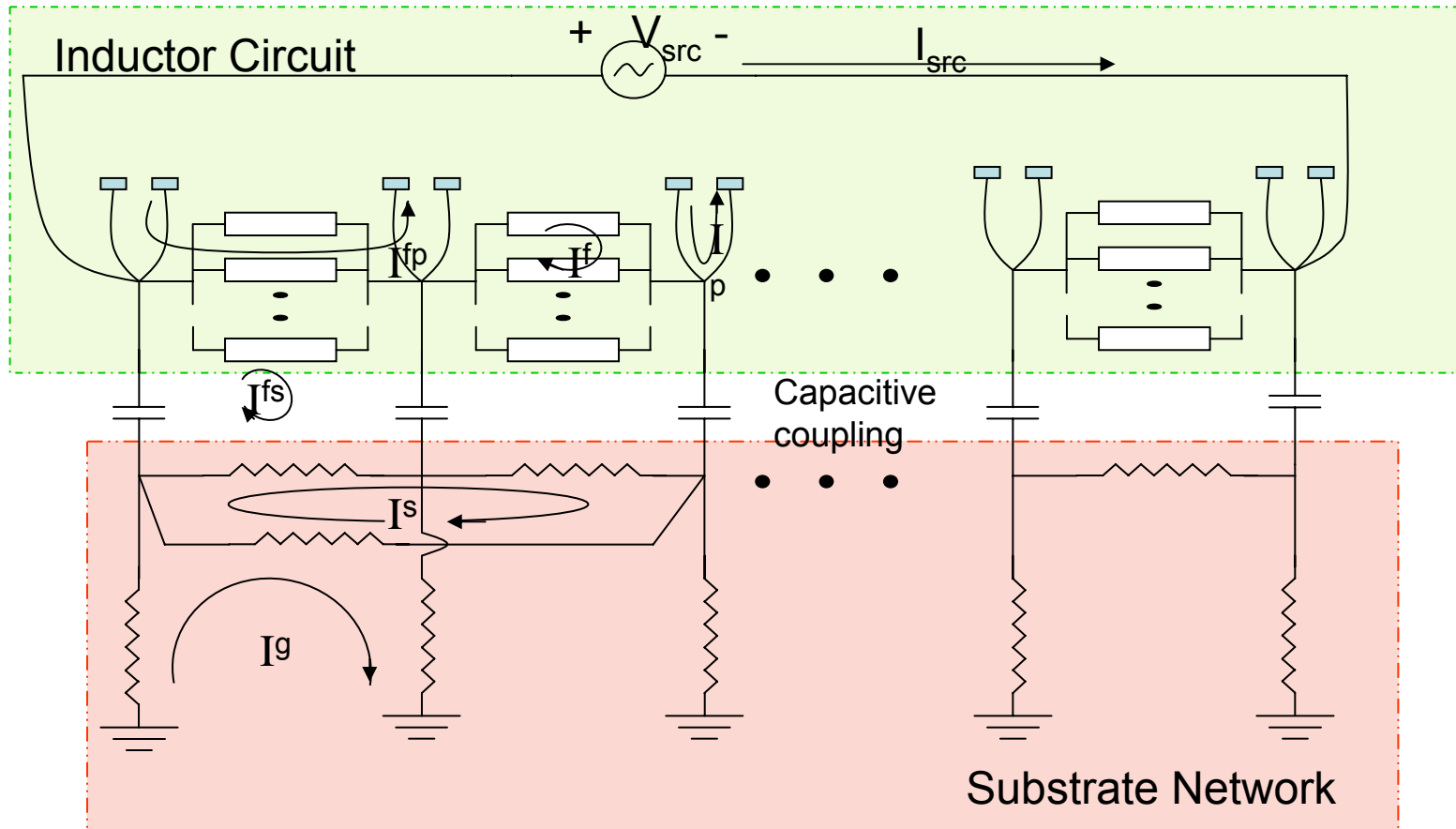
$$R_{ij} = \frac{1}{C_{ij}}$$


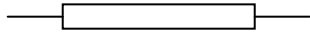



Substrate Contact Modelling



Substrate Modeling



-  Panels
-  Inductor Impedances ¹⁷
-  Substrate resistances

Modeling Equations

$$\begin{bmatrix}
 Z_m^f & Z_m^{fp} & Z_m^{fp} & 0 & 0 & 0 & 0 & 0 \\
 Z_m^{fp^T} & Z_m^p & Z_m^{fp} & 0 & 0 & 0 & M^{ps} & 0 \\
 Z_m^{fp^T} & Z_m^p & Z_m^{fp} + Z_m^{fs} & -Z_m^{gs} & -Z_m^{fs} & 0 & 0 & M^{cs} \\
 0 & 0 & -Z_m^{fs^T} & Z_m^g & Z_m^{fs} & 0 & 0 & 0 \\
 0 & 0 & -Z_m^{fs^T} & Z_m^{fs^T} & Z_m^s & 0 & 0 & 0 \\
 0 & 0 & 0 & 0 & 0 & 0 & M^p & 0 \\
 0 & -pM^{ps^T} & 0 & 0 & 0 & -pM^{p^T} & sI & 0 \\
 0 & 0 & -p_c M^{c^T} & 0 & 0 & 0 & 0 & sI
 \end{bmatrix}
 \begin{bmatrix}
 I_m^f \\
 I_m^{fp} \\
 I_m^{fs} \\
 I_m^{sg} \\
 I_m^s \\
 I_m^p \\
 V_b^p \\
 V_b^c
 \end{bmatrix}
 =
 \begin{bmatrix}
 V_b^f \\
 V_b^{fp} \\
 V_b^{fs} \\
 V_b^{sg} \\
 V_b^s \\
 V_b^p \\
 0 \\
 0
 \end{bmatrix}$$

$$sLx = -Rx + BV_{src}$$

PEEC CIRCUIT

$$sLx = -Rx + BV_{src}$$


- Let,

$$E = sL + R$$

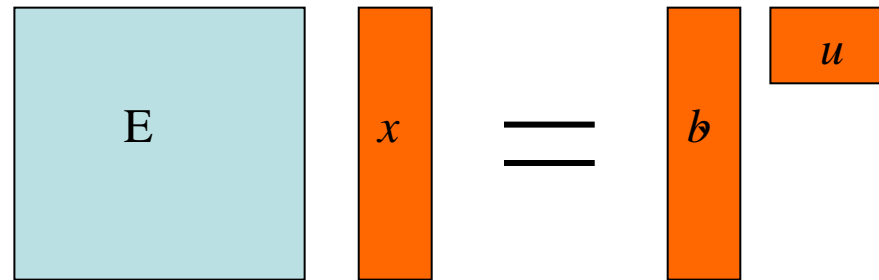
$$\Rightarrow Ex = Bu$$

- Size of E can be prohibitively large.
- E is constructed from scratch in each iteration.
- Equation need to be solved every time configuration is changed.

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Parameterization



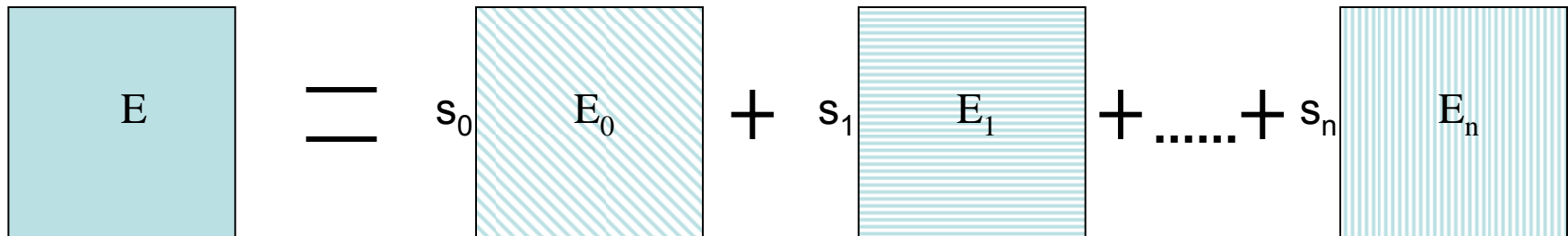
A diagram showing a light blue square matrix labeled E multiplied by an orange vertical vector labeled x . This is followed by an equals sign, then an orange vertical vector labeled b and a small orange square labeled u .

$$E x = b + u$$



$$s_i = \{1, d, W, dW, d^2, W^2\}$$

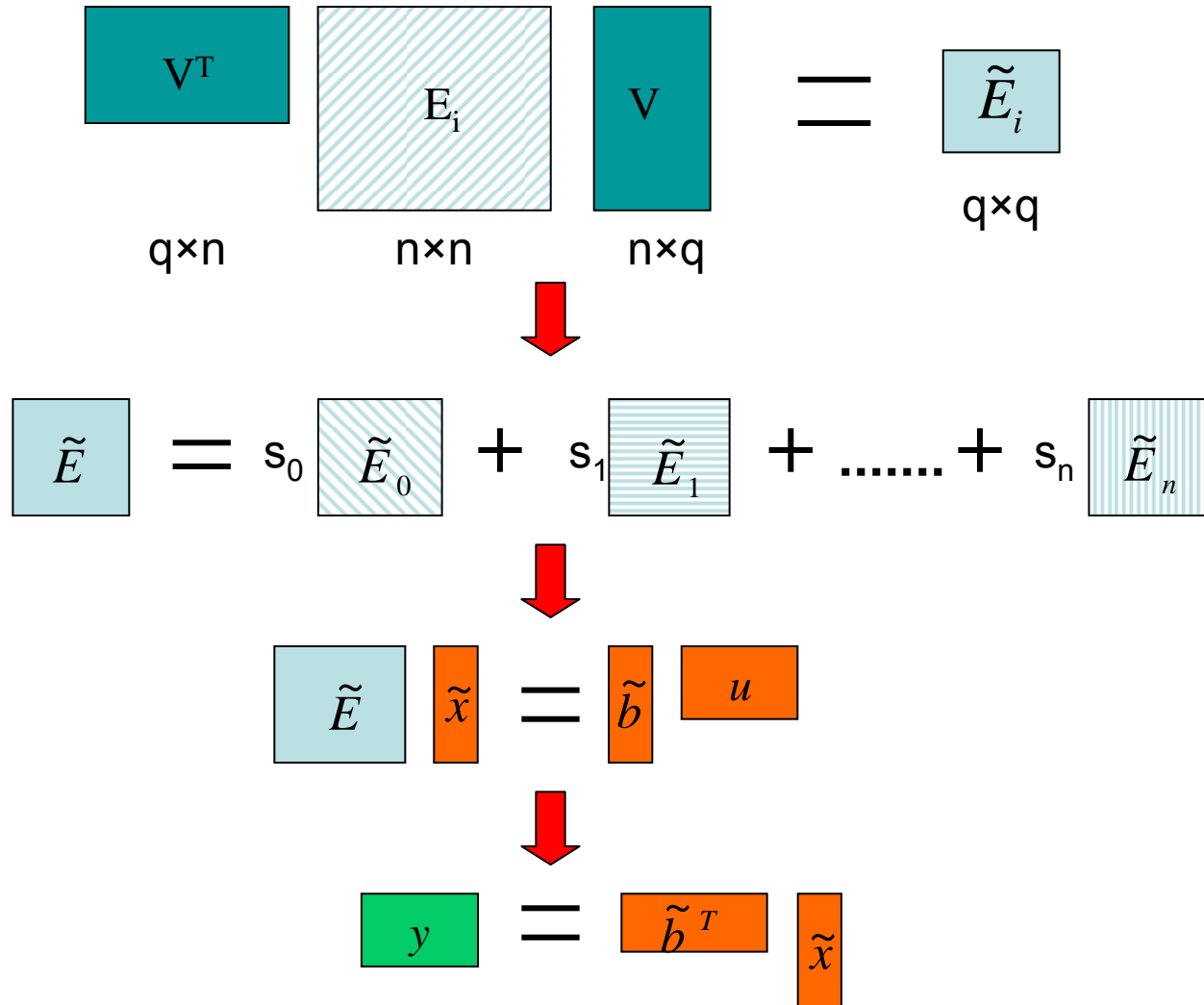




A diagram showing a light blue square matrix labeled E followed by an equals sign. To the right of the equals sign is a sum of terms: $s_0 E_0$, $s_1 E_1$, followed by an ellipsis, and $s_n E_n$. Each E_i is a square matrix with a different hatching pattern: E_0 has diagonal hatching, E_1 has horizontal hatching, and E_n has vertical hatching.

$$E = s_0 E_0 + s_1 E_1 + \dots + s_n E_n$$

Model Reduction



Control Flow

- Compute \tilde{E}_i from a set of sample points (w_i, d_i) .
- New configuration : $W_1 \longrightarrow W_2, d_1 \longrightarrow d_2$
 - $s_i \in \{1, d_2, W_2, d_2 W_2, d_2^2, W_2^2, s, s d_2, s W_2, s d_2 W_2, s d_2^2, s W_2^2\}$.
 - Compute new \tilde{E} :

$$\tilde{E} = s_0 \tilde{E}_0 + s_1 \tilde{E}_1 + \dots + s_n \tilde{E}_n$$

- Solve for y .

$$\tilde{E} \tilde{x} = \tilde{b} u$$

$$y = \tilde{b}^T \tilde{x}$$

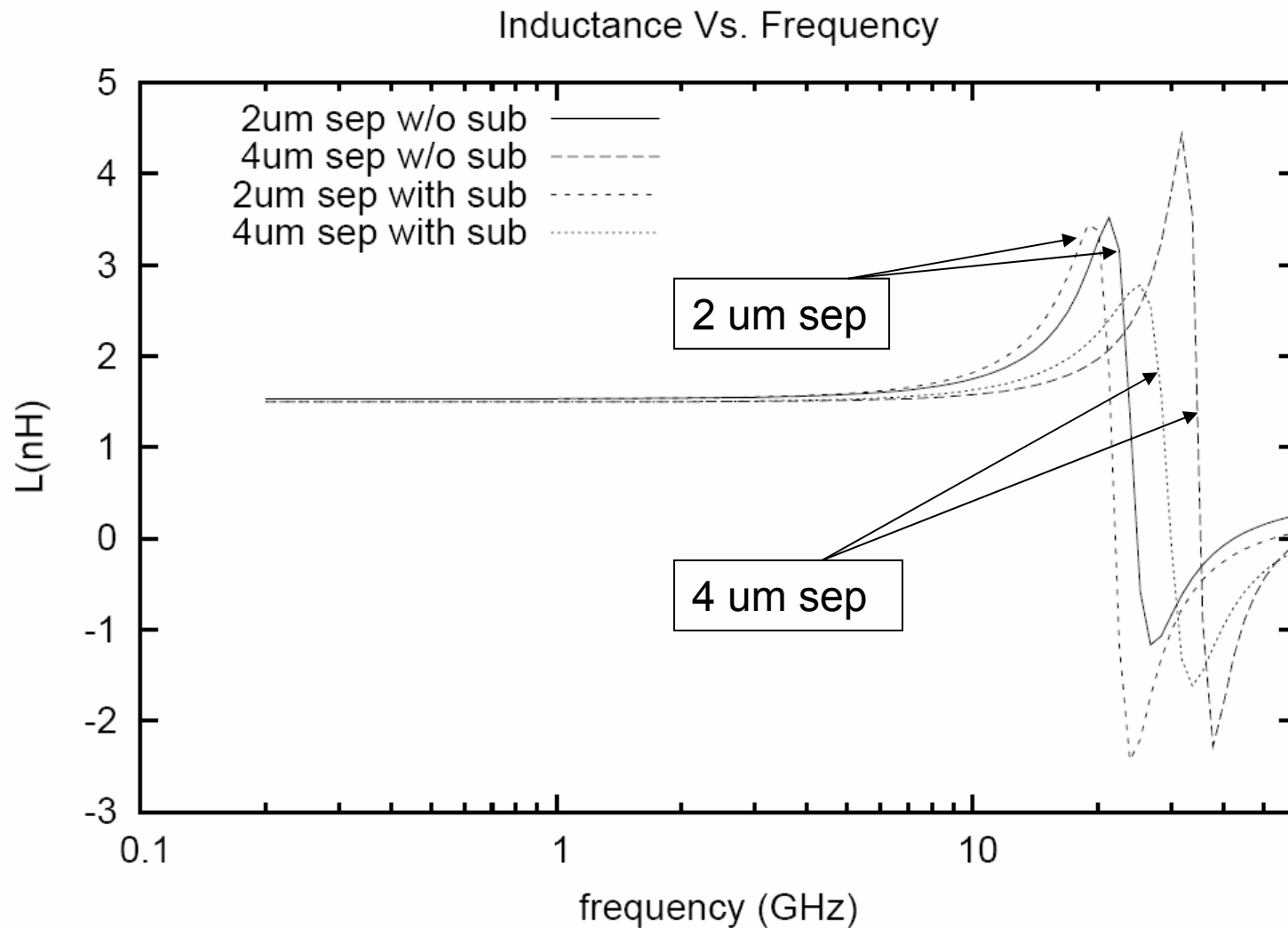
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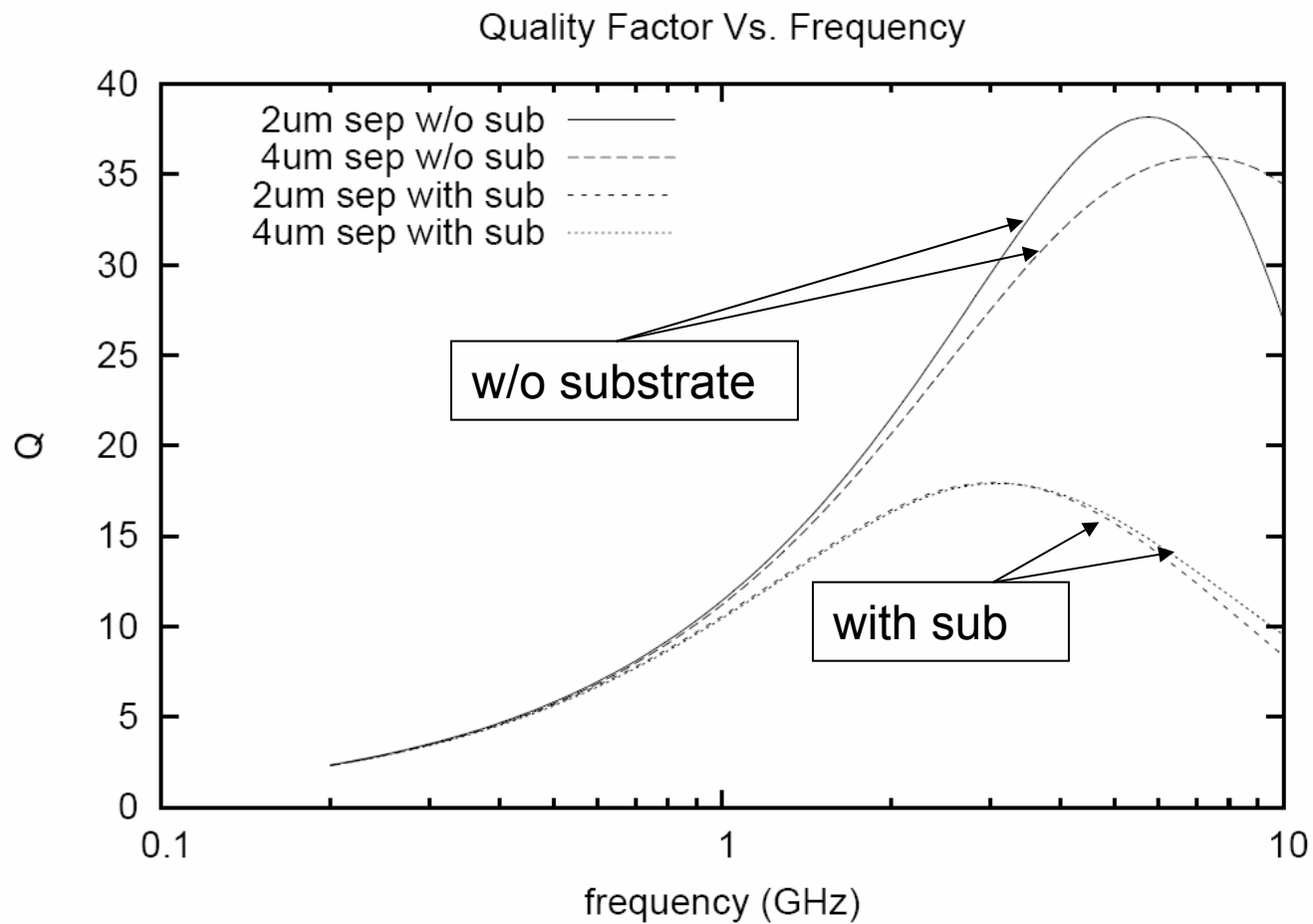
Results

- Conclusions & Future Work

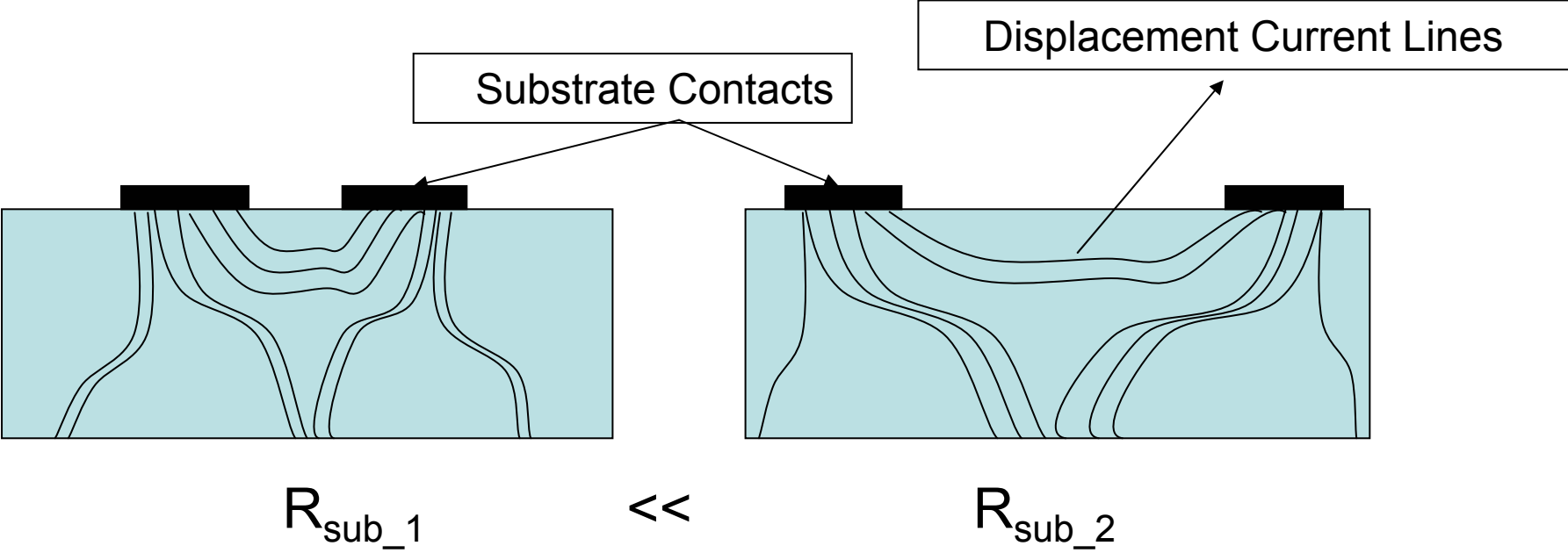
Results : Effects of Substrate on Inductance



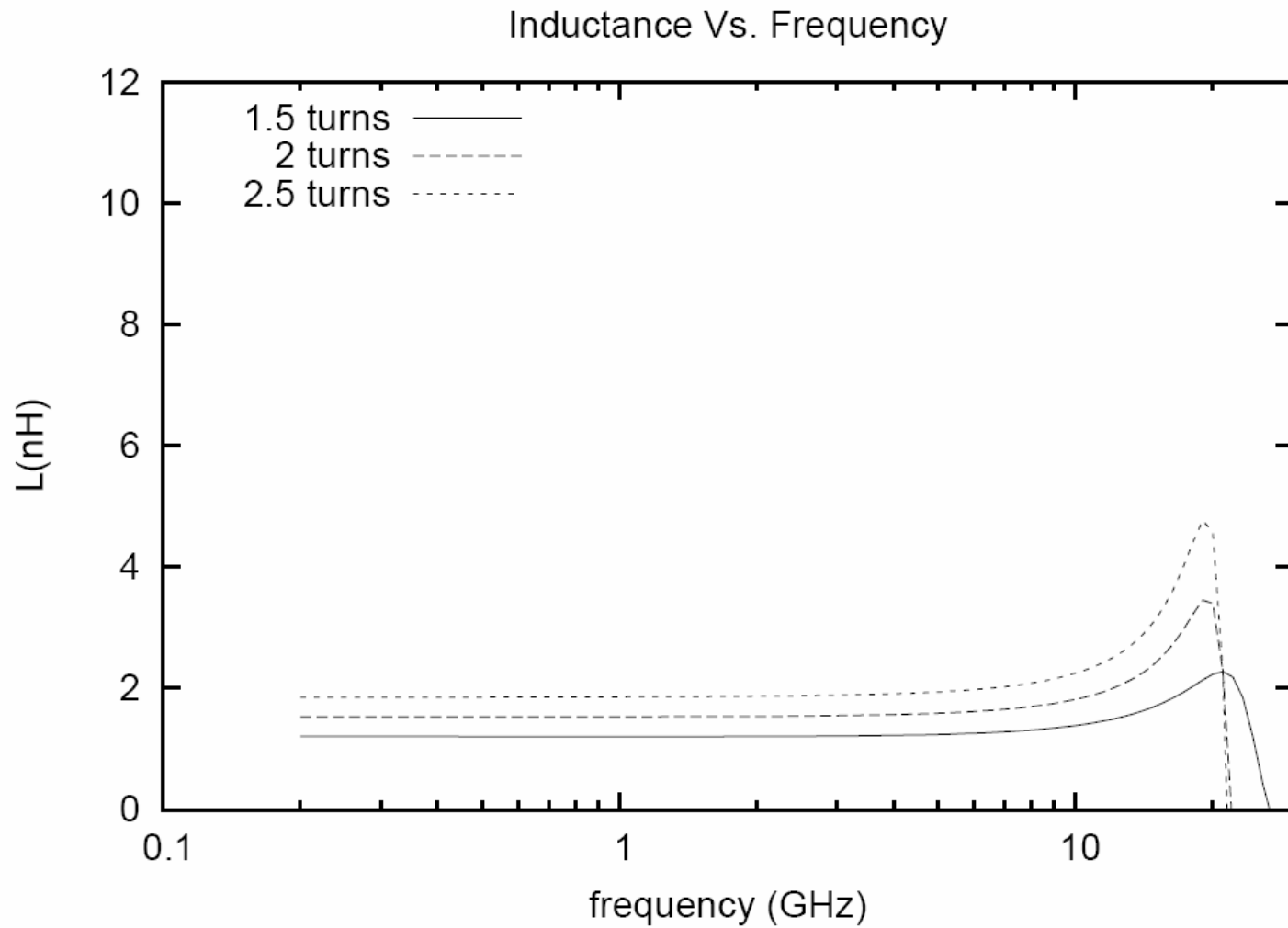
Results : Effects of Substrate on Quality Factor



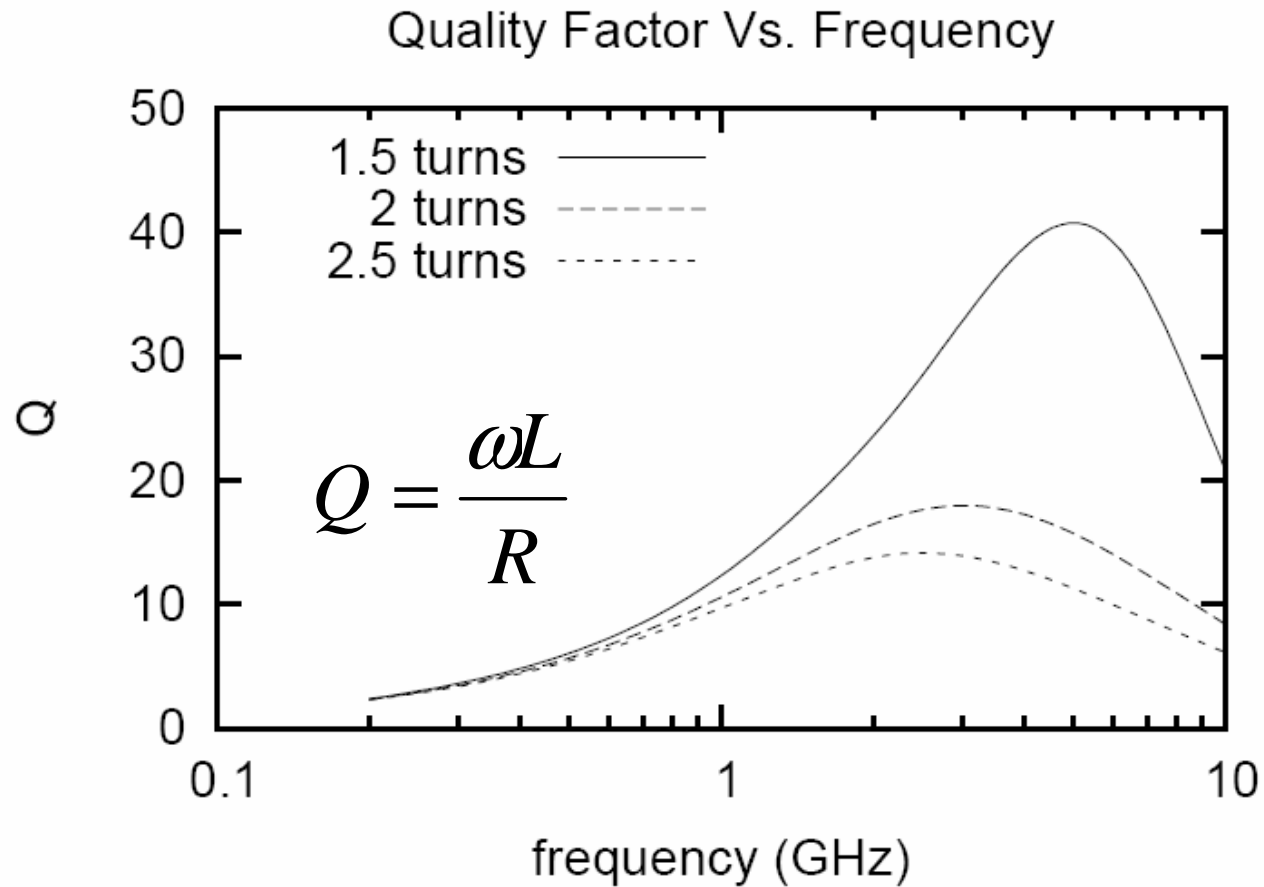
Effects of Separation B/W Turns



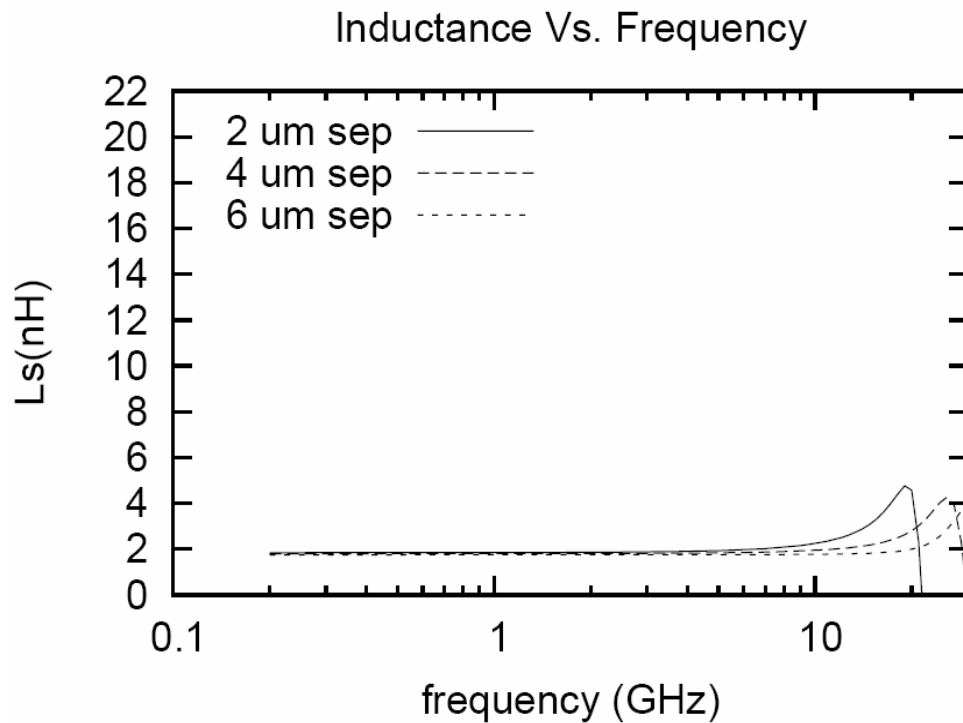
Results : Number of Turns



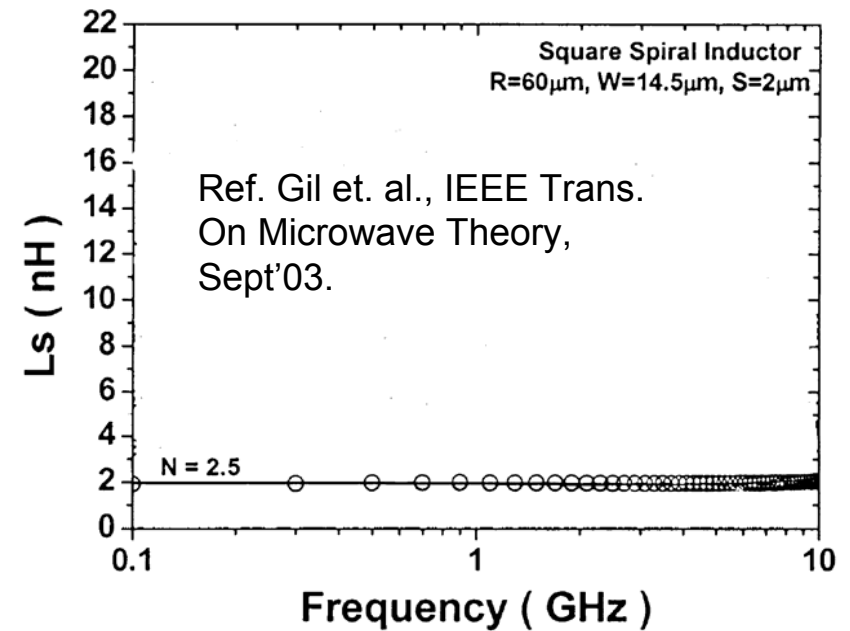
Results : Number of Turns



Results : Simulated Vs Measured Inductance

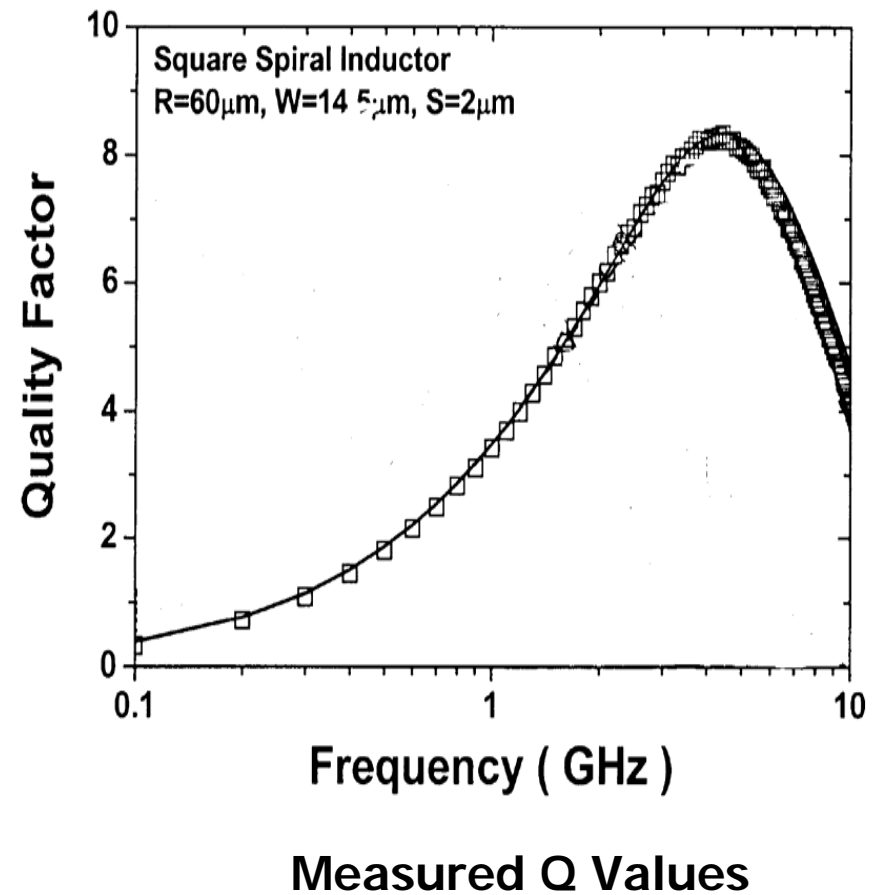
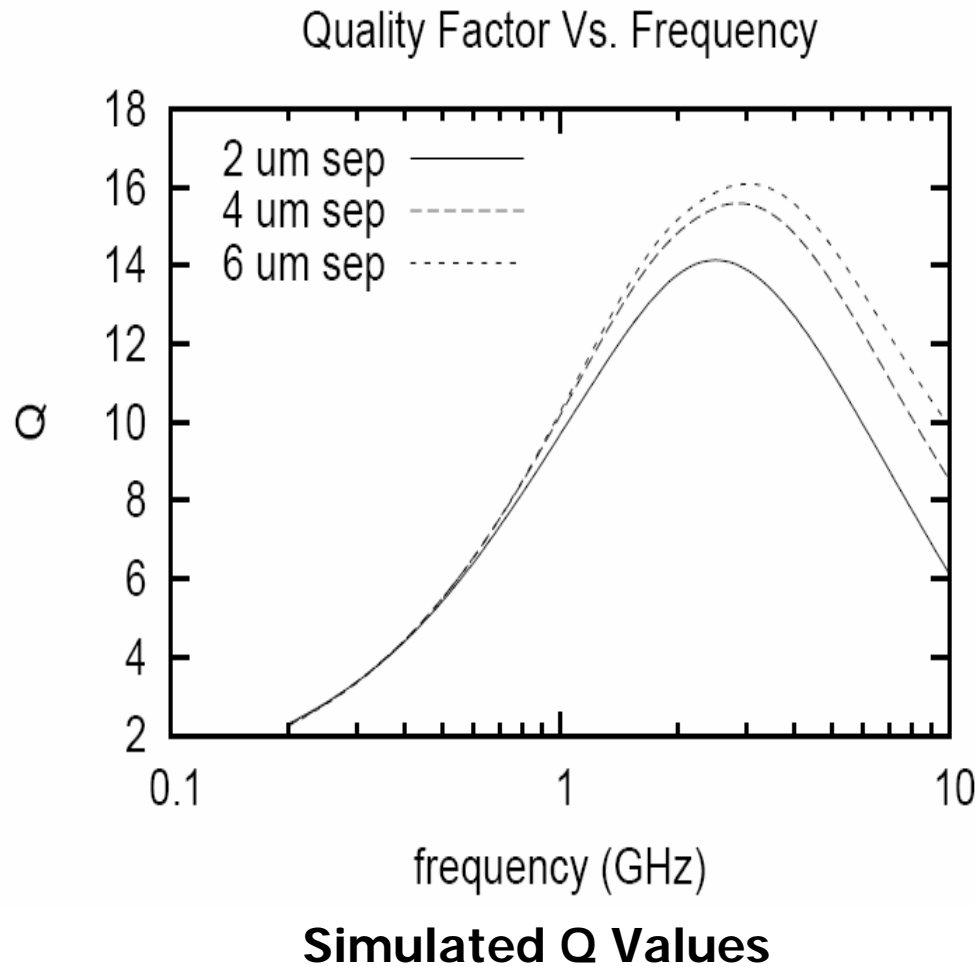


Simulated Inductance



Measured Inductance

Results : Simulated Vs Measured Quality Factor

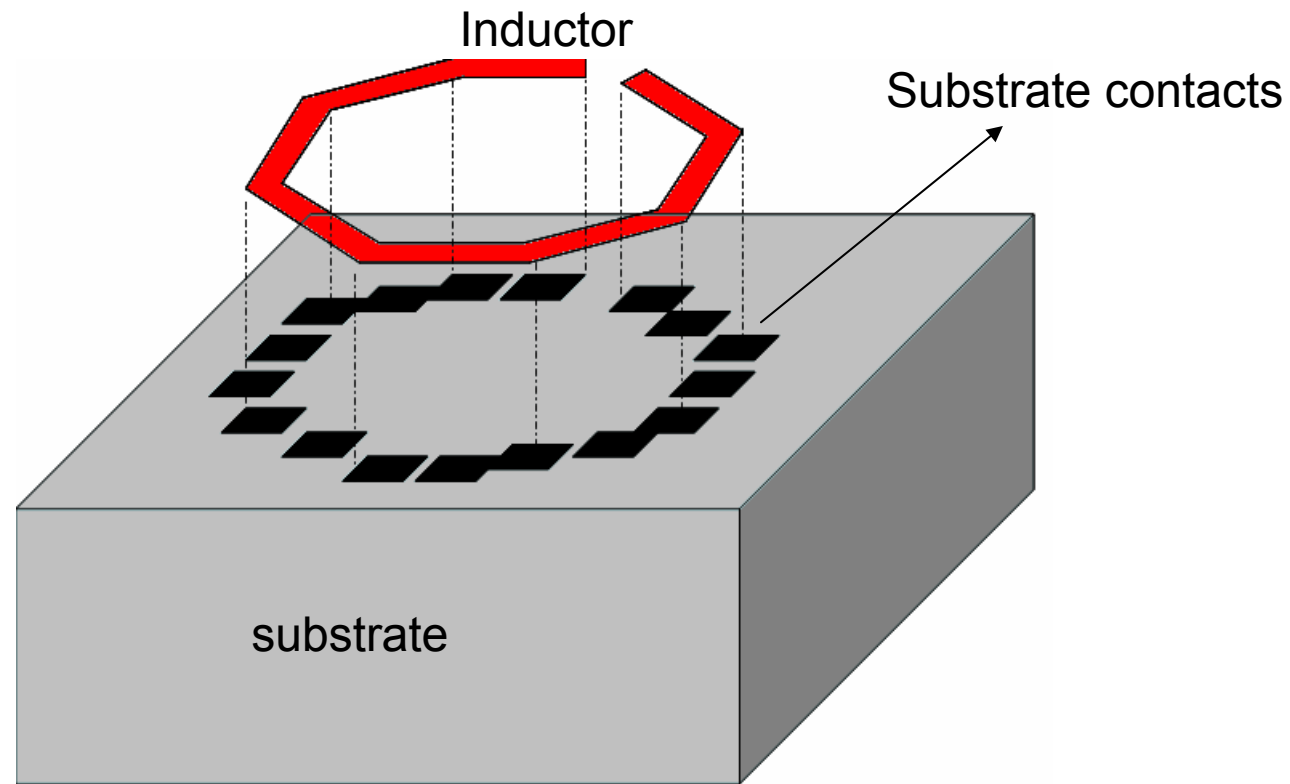


CPU Time

- 2 GHz Intel Pentium 4 processor
- 1 GB RAM

Configuration	w/o param	with param
1 turn (10 config)	15 min/config	15 min + 2 sec/config
2 turns (10 config)	35 min/config	35 min + 2 sec/config
2.5 turns (10 config)	50 min/config	60 min + 2 sec/config

Modeling Octagonal Shapes



Octagonal RF Inductor

Outline

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- ➔ **Conclusions & Future Work**

Conclusion

- A substrate aware parameterization technique has been proposed.
- The substrate has a significant impact on quality of RF inductors.
- The simulator accurately models the inductance.
- The small discrepancy in Q is due to inability to model via resistances.

Future Work

- Scheme to model “via” resistance.
- Include Eddy Current effects in model.
- Make the model efficient
 - Using standard sparse matrix packages.
 - Optimizing on matrix operations.

Thank You